

Notice of References Cited			Application No. 09/362,504	Applicant(s) Kramadhati et al		
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U	Jin Onuki et al,"High-reliability interconnection formation by a two-step switching bias sputtering process",Thin Solid Films, 182-188					1/1995
V	H. Ramarotafika et al,"Influence of a d.c. substrate bias on the resistivity, composition, crystallite size and microstrain of WTi and WTi-N films",Thin Solid Films, 267-273					1/1995
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